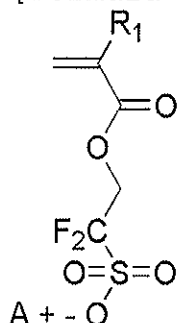


ABSTRACT

ONIUM SALT COMPOUND, POLYMER COMPOUND COMPRISING THE SALT COMPOUND, CHEMICALLY AMPLIFIED RESIST COMPOSITION COMPRISING THE POLYMER COMPOUND, AND METHOD FOR PATTERNING USING THE COMPOSITION

A compound represented by the following formula (1) is provided:

[Formula 1]



wherein R1 and A are defined in the Specification.

The chemically amplified resist composition comprising a polymer compound which is produced from the compound of formula 1 according to the present invention provides a chemically amplified resist sensitive to far-ultraviolet radiation. The resist composition is less dependent on the substrate, and has excellent adhesiveness, excellent transparency in the subject wavelength region, and excellent dry etch resistance, and a resist pattern excellent in sensitivity, resolution and developability can be formed from the resist composition.

Figure 1.